IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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37 CFR § 1.8.

Mary Carrillo

Confirmation No. 5813

Applicant : Nam Hun Kim Application No. : 10/593,857

: September 22, 2006

Title : PLASMA CHAMBER HAVING PLASMA SOURCE COIL AND

METHOD FOR ETCHING THE WAFER USING THE SAME

Grp./Div. : 1792

Filed

Examiner : Duy Vu Nguyen Deo

Docket No. : 58409/N305

RESPONSE TO RESTRICTION REQUIREMENT / ELECTION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 Post Office Box 7068 Pasadena, CA 91109-7068 April 17, 2008

Commissioner:

In response to the Office action dated March 18, 2008, applicant hereby elects Group I, claims 1-6.

Applicants reserve the right to pursue the non-elected (withdrawn) claims in a Divisional application.

Respectfully submitted,

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By

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